

11/15 演講公告

Title: Atomistic Guided Development of Hard Thin Films for Severe Applications

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ABSTRACT

This work summarizes recent developments on applying thin film structure and architecture concepts to hard coatings for optimized performance in various application fields.

The hardness of materials rapidly decreases at elevated temperatures as generally the density of structural defects, such as point defects, dislocations, and grain boundaries, decreases. Additional strengthening can be provided by age-hardening mechanisms, which originate from decomposition-processes of supersaturated phases to form new obstacles retarding plastic deformation. Furthermore important is the resistance against oxidation and corrosive attack.

By using ab initio calculations and sophisticated experimental methods we will have a detailed insight into various mechanisms responsible for excellent mechanical strength, thermal stability and oxidation resistance properties of Ti–Al–N based hard coatings. For these materials we will also compare the effect of various architecture and alloying concepts with e.g., Y, Zr, Hf, Nb, and Ta.

The various thin film structure and architecture concepts allow the utilization of multifunctional properties facilitating the development of next generation's hard coatings.

Keywords: nitride thin films, thermal stability, alloying concepts, density functional theory

Room: E1-242 & Time: 0900-1100

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